

A compact and versatile vacuum coating system for r+d thin film applications.

Featuring clean pumping technology, the R N D was designed specifically to address cutting edge prototype and research applications. The R N D features a high quality, fully Helium leak tested chamber. The system design maximises the space and configuration options available.

As an independent system integrator, Wordentec selects quality components from a range of respected world class suppliers.

FerroTec

PFEIFFER VACUUM

CTI-CRYOGENICS
HEAT TREATMENT CORPORATION

mks
Technology for Productivity

Rockwell
Automation
Allen-Bradley

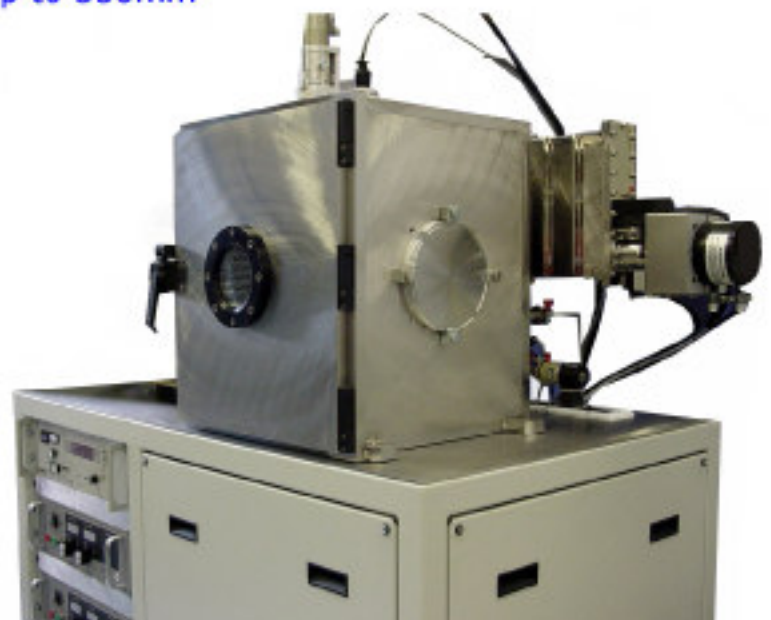
AE ADVANCED
ENERGY
Atomic Technology, Atomic Precision

Features:

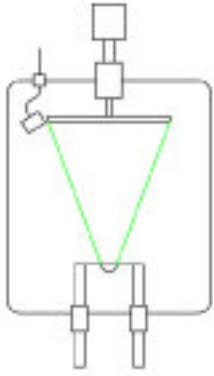
- High quality 400 mm stainless steel chamber
- Industry standard clean pump group (Cryo and Turbo options)
- Robust PLC control
- Removable chamber liners
- Source - substrate distance up to 350mm

Options:

- Pumped substrate load lock
- Substrate rotation
- Substrate heating
- Substrate cooling
- Shutters
- Film thickness monitoring
- Chamber cooling
- Custom chamber design
- Glove box integration
- PC interface



RND COATING SYSTEM

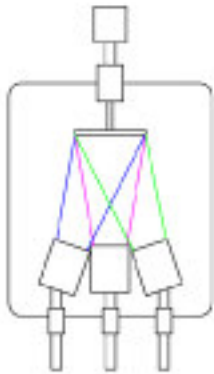
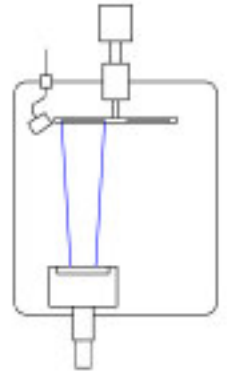


Thermal Evaporation

single source
multiple source
crystal monitoring
source sequencing

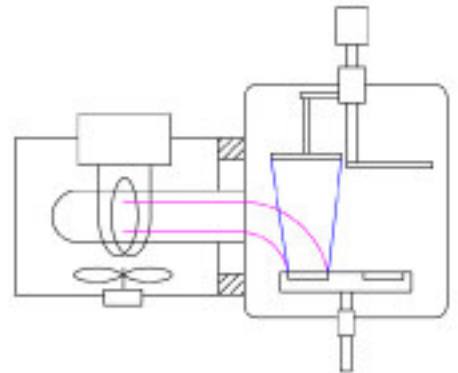
Electron Beam Deposition

high quality sources
multiple pocket
single pocket
digital scan



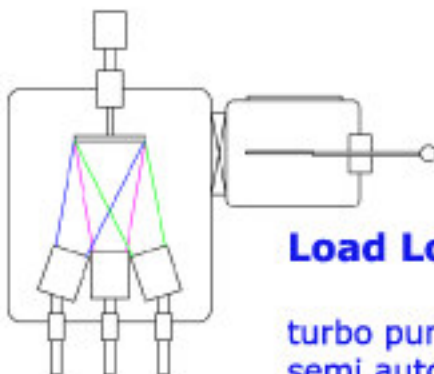
Magnetron Sputtering

single / multiple source
multiple gas inlet
co-sputtering
sequential sputtering



HiTUS[®] Remote Plasma

high target utilization
metal / dielectric sputtering
high density plasma
compact design



Load Lock

turbo pump load lock
semi automatic operation
adaptable sample carrier
fast cycle times

WORDENTEC

7 Devon Units
Hatchmoor Industrial Estate
Great Torrington
Devon EX38 7HP
44(0)1805 625309
www.wordentec.com

